

SU-8 3025 – run sheet

Kayaku MicroChem / MicroChem Corp.

nanyte.com/photoresists/su-8-3025 · last updated 2026-07-26

Softbake: 95 °C · hotplate

Exposure dose – dose by film thickness

Film thickness	Dose
4–10 µm	100–200 mJ/cm ²
8–15 µm	125–200 mJ/cm ²
20–50 µm	150–250 mJ/cm ²
30–80 µm	150–250 mJ/cm ²
40–100 µm	150–250 mJ/cm ²

Post-exposure bake: 95 °C

Develop: Developer SU-8 Developer (MicroChem's proprietary solvent-based developer); ethyl lactate and diacetone alcohol are also stated to work · Rinse Spray/wash with fresh SU-8 developer for ~10 s, then a second spray/wash with isopropyl alcohol (IPA) for ~10 s, then air/nitrogen dry with filtered pressurized gas. A white film appearing during the IPA rinse indicates under-development – immerse or spray with more SU-8 developer and repeat the rinse. Ultrasonic or megasonic bath agitation is recommended for developing out vias/holes in high-aspect-ratio structures.

Hardbake: 150–200 °C